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Sust 29, 2005

TOWNSEND and TOWNSEND and CREW LLP

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:

VEERASAMY, VIJAYEN, et al.

Application No.: 10/773,796

Filed: February 6, 2004

For: RECORDING MEDIA HAVING PROTECTIVE OVERCOATS OF HIGHLY TETRAHEDRAL AMORPHOUS CARBON AND METHODS FOR THEIR PRODUCTION Examiner: PADGETT, Marianne L.

Art Unit: 1762

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT UNDER 37

CFR §1.97 and §1.98

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

The references cited on attached form PTO/SB/08A&B are being called to the attention of the Examiner. Copies of the references [in compliance with the requirements of 1287 OG 163] are enclosed.

It is respectfully requested that the cited references be expressly considered during the prosecution of this application, and the references be made of record therein and appear among the "references cited" on any patent to issue therefrom.

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Page 2

As provided for by 37 CFR 1.97(g) and (h), no inference should be made that the information and references cited are prior art merely because they are in this statement and no representation is being made that a search has been conducted or that this statement encompasses all the possible relevant information.

This IDS is being filed before the mailing date of the final Office Action or Notice of Allowance.

Please charge the IDS fee of \$180 to Deposit Account No. 20-1430. Please deduct any additional fees from, or credit any overpayment to, the above-noted Deposit Account.

Respectfully submitted,

Nena Bains Reg. No. 47,400

TOWNSEND and TOWNSEND and CREW LLP Two Embarcadero Center, Eighth Floor San Francisco, California 94111-3834

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INFORMATION DISCLOSURE STATEMENT BY APPLICANT

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	Complete if Known
Application Number	10/773,796
Filing Date	February 6, 2004
First Named Inventor	Veerasamy, Vijayen
Art Unit	1762
Examiner Name	PADGETT, Marianne L.
Attorney Docket Number	014089-002580US

U.S. PATENT DOCUMENTS+						
		Document Number				
Examiner Initials*	Cite No.1	Number Kind Code ² (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	

				FOREIGN PA	TENT DOCUME	ENTS		
Examiner	Cite	Foreign Patent Document			Name of Patentee or	Pages, Columns, Lines,		
Initials*	No.1	Country Code ³	Number⁴	Kind Code ⁵ (if known)	Publication Date MM-DD-YYYY	Applicant of Cited Document	Where Relevant Passages or Relevant Figures Appear	T⁰
	0001	EP	0 552 491	A1	07-28-1993	Collins et al.		
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		NON PATENT LITERATURE DOCUMENTS	
Examiner Initials *	Cite No.1	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T 2
	0008	Aisenberg, S. et al.; "Ion-Beam Deposition of Thin Films of Diamondlike Carbon;" J. Appl. Phys.; June 1971; pp. 2953-2958; vol. 42; No. 7.	
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Examiner	Date
Signature	Considered

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Substitute	for form 1449A&B/	РТО			Complete if Known
INICO		DIC	CI OCUDE	Application Number	10/773,796
INFORMATION DISCLOSURE			•	Filing Date	February 6, 2004
STATEMENT BY APPLICANT		First Named Inventor	Veerasamy, Vijayen		
			Art Unit	1762	
(0	ise as many sh	eets as	necessary)	Examiner Name	PADGETT, Marianne L.
Sheet	2	of	2	Attorney Docket Number	014089-002580US

		NON PATENT LITERATURE DOCUMENTS	
Examiner Initials *	Cite No.1	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T 2
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